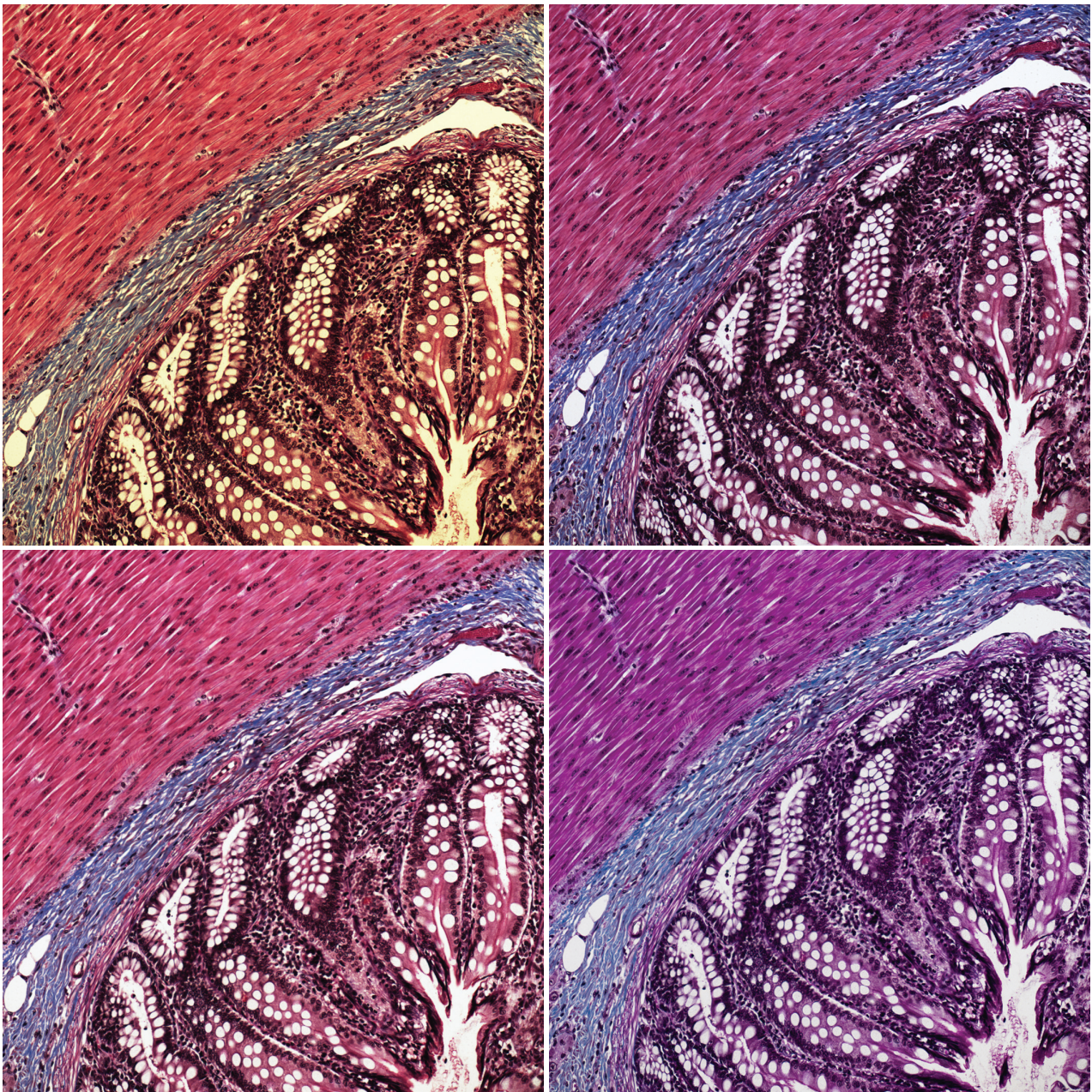


# Microscopy TODAY

Volume 22 Number 1 2014 January

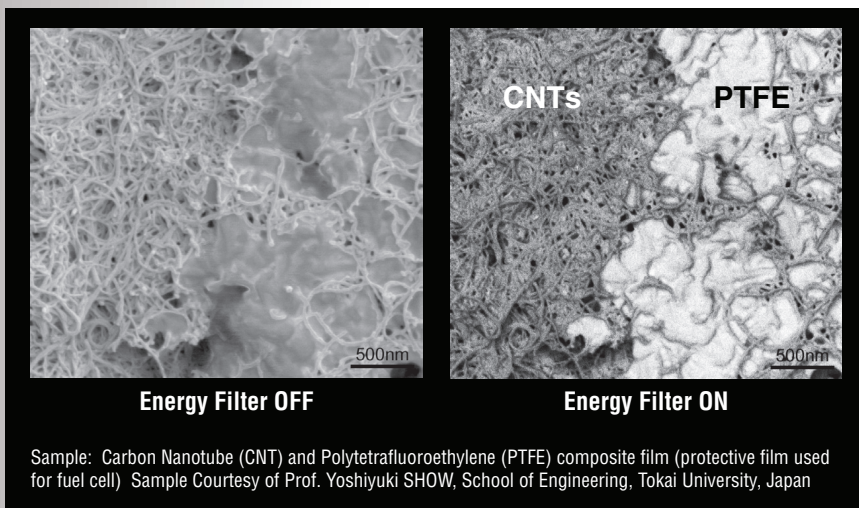


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**Image at Top:** Cathodoluminescence image of composite SiC-diamond cutting tool; Colin MacRae, CSIRO-Minerals, Clayton, Victoria, Australia

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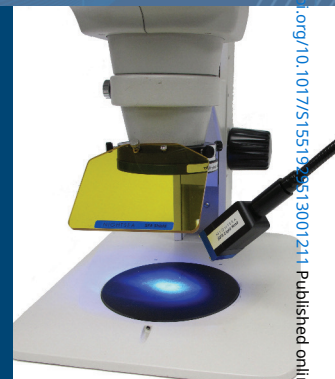
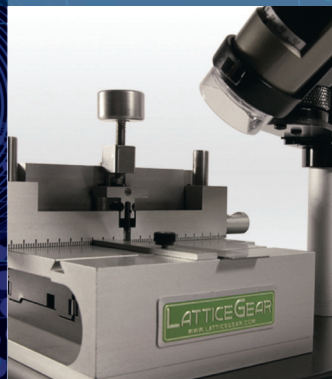
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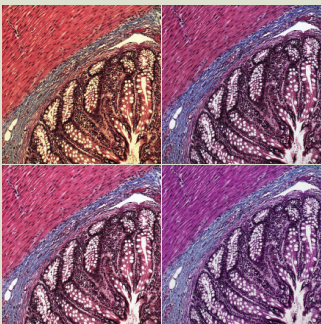
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### About the Cover



Color measurement and correction for light microscopy. Image width = 750  $\mu$ m.

See article by Foster and Sedgewick.

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